

Optimal binary gratings for multi-wavelength magneto-optical traps – Supplementary material

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<https://eqop.phys.strath.ac.uk/atom-optics/grating-mots>

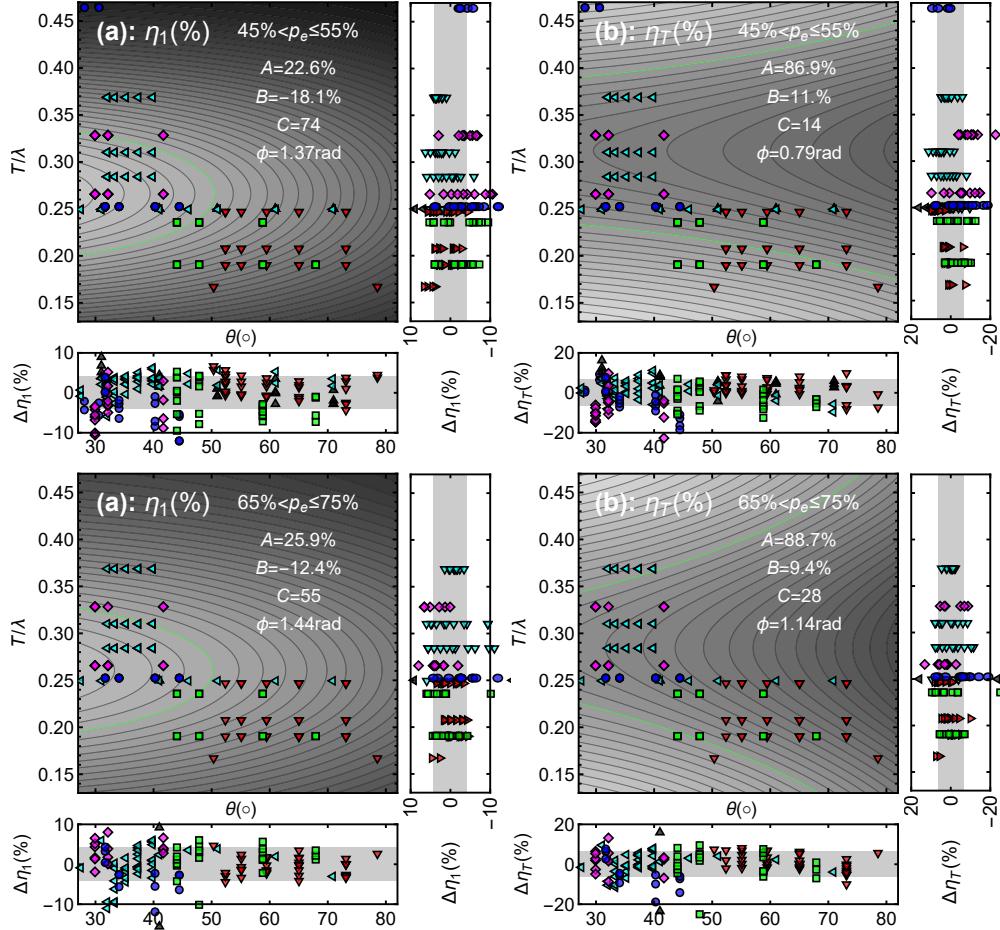


Fig. S1. This figure is the equivalent of Fig. 2 in the main paper, but instead illustrates η_1 and η_r with grating etch duty ranges $45\% < p_e \leq 55\%$ (upper row) and $65\% < p_e \leq 75\%$ (lower row).

To explore how variation of the empirical fit may be a function of the finite range of duty cycles in the fit, we have also investigated duty ranges of 5%, halving the ranges we used in the paper. This leads to the empirical surface fit parameters in Table S1.

p_e	A_1	B_1	C_1	ϕ_1	$\Delta\eta_1$	A_t	B_t	C_t	ϕ_t	$\Delta\eta_t$
50	22.6	-18.1	74	1.37	4.1	86.9	11.6	14	0.79	6.6
60	23.2	-18.7	58	1.41	3.2	89.2	8.2	27	0.91	5.6
70	25.9	-12.4	55	1.44	4.2	88.7	9.4	28	1.14	6.5
47.5	21.2	-19.0	82	1.36	4.4	85.2	11.4	5.0	0.80	7.1
52.5	26.5	-14.4	66	1.37	3.1	90.6	12.3	27	0.82	5.6
57.5	23.0	-20.3	65	1.43	3.1	90.4	8.4	31	0.73	5.5
62.5	26.7	-13.2	52	1.38	2.9	89.0	9.8	22	1.16	5.5
67.5	25.1	-14.1	50	1.39	3.7	88.8	7.5	30	0.99	5.3
72.5	26.7	-11.1	61	1.51	4.4	89.1	11.4	28	1.18	7.1

Table S1. The fitted surfaces for η_1 (left, subscript 1) and η_t (right, subscript t), with corresponding RMS fit errors $\Delta\eta_1$, $\Delta\eta_t$. All units are the same as Table 2 in the paper. The p_e values given are the centre of the: $\pm 5\%$ etch duty range (first three rows, duplicating the values in Table 1 of the paper for comparison); $\pm 2.5\%$ etch duty range (last six rows). The number of laser-grating combinations used for the fits in the last six lines of the table were 94, 80, 117, 86, 57, and 67, respectively.

The fit to η_0 directly using Eq. 1 in the paper led to a slightly worse RMS error to experiment than inferring the value from the two other fits via $\eta_0 = \eta_t - 2\eta_1$. We note this discrepancy can be removed by adding an extra term to the fit function:

$$\eta_i = (1 - C_i \theta^2)(A_i + B_i \sin(\phi_i + 4\pi T/\lambda) - \zeta T/\lambda), \quad (\text{S1})$$

where ζ is a positive dimensionless parameter approximately describing a drop in diffraction efficiency with etch depth. The fit residues for η_1 and η_t in Table S1 barely decrease ($\approx 0.1\%$ change) if the enhanced fit function of Eq. S1 is used. However, both the inferred and particularly the direct η_0 fit residues are improved and then differ by only $\approx 0.3\%$ – although the inferred $\eta_0 = \eta_t - 2\eta_1$ still has the lowest residue of $3\% < \Delta\eta_0 < 5\%$.

In the remainder of this Supplement we check for any possible remaining trends in the fit residues, but find no strong correlations. We ensure there is no strong variation with laser wavelength, grating diffraction angle or dimensionless grating etch depth, as illustrated in Figs. S2-S4, respectively. Each plot has 6 rows corresponding to the 5% etch duty ranges in Table S1, with the left, middle and right columns show the residues of η_t , η_1 , and inferred $\eta_0 = \eta_t - 2\eta_1$.

We have also determined how much variance there is in diffraction efficiency for the ‘same grating’ in terms of all three dimensionless grating parameters of etch duty, diffraction angle and etch depth parameters with binning ranges of 5%, 4°, and 2.5% respectively. This yields RMS variations in η_t , η_1 , and inferred η_0 of approximately 3.6%, 2.3% and 2.6%, respectively.

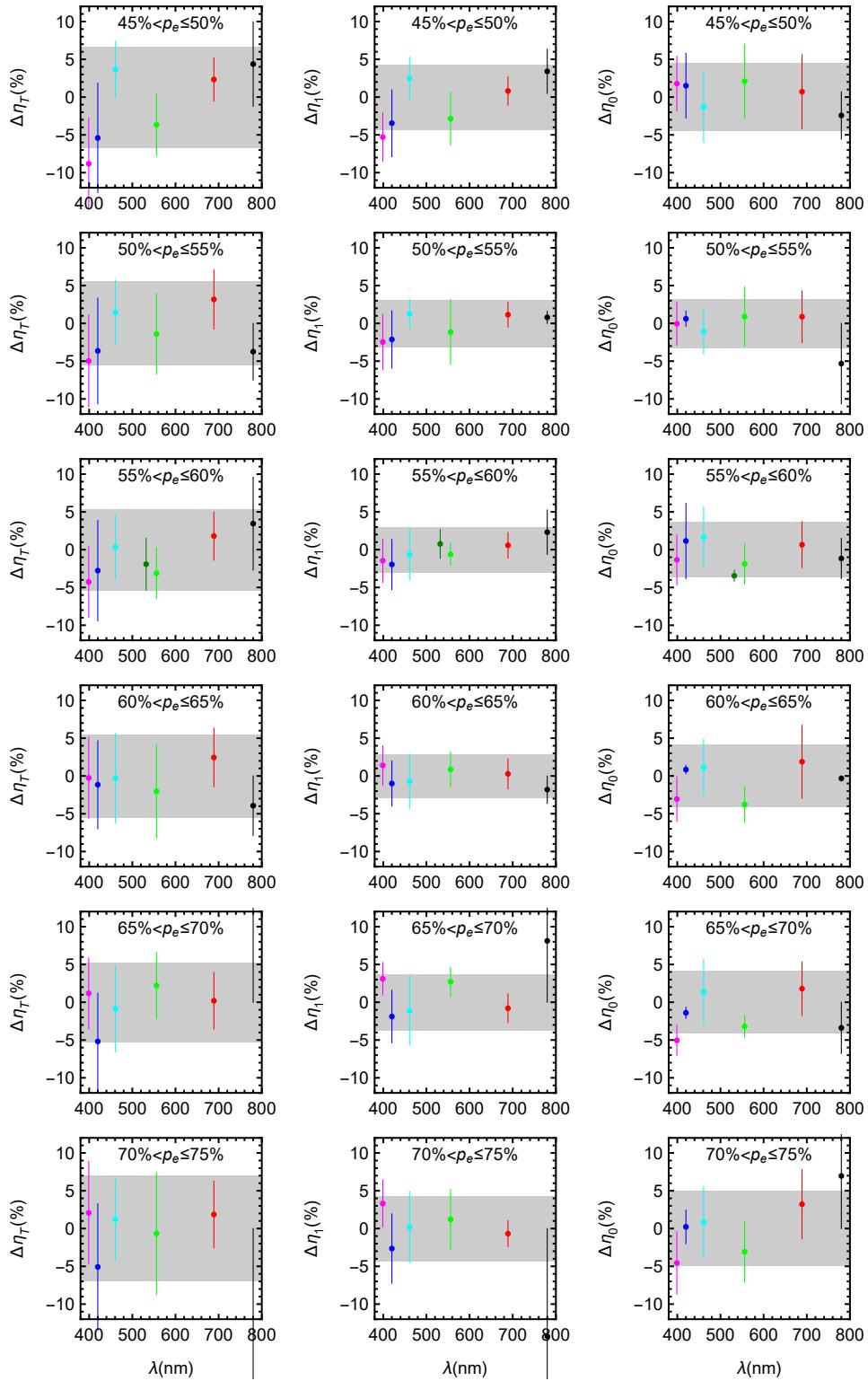


Fig. S2. Fit residuals as a function of testing laser wavelength.

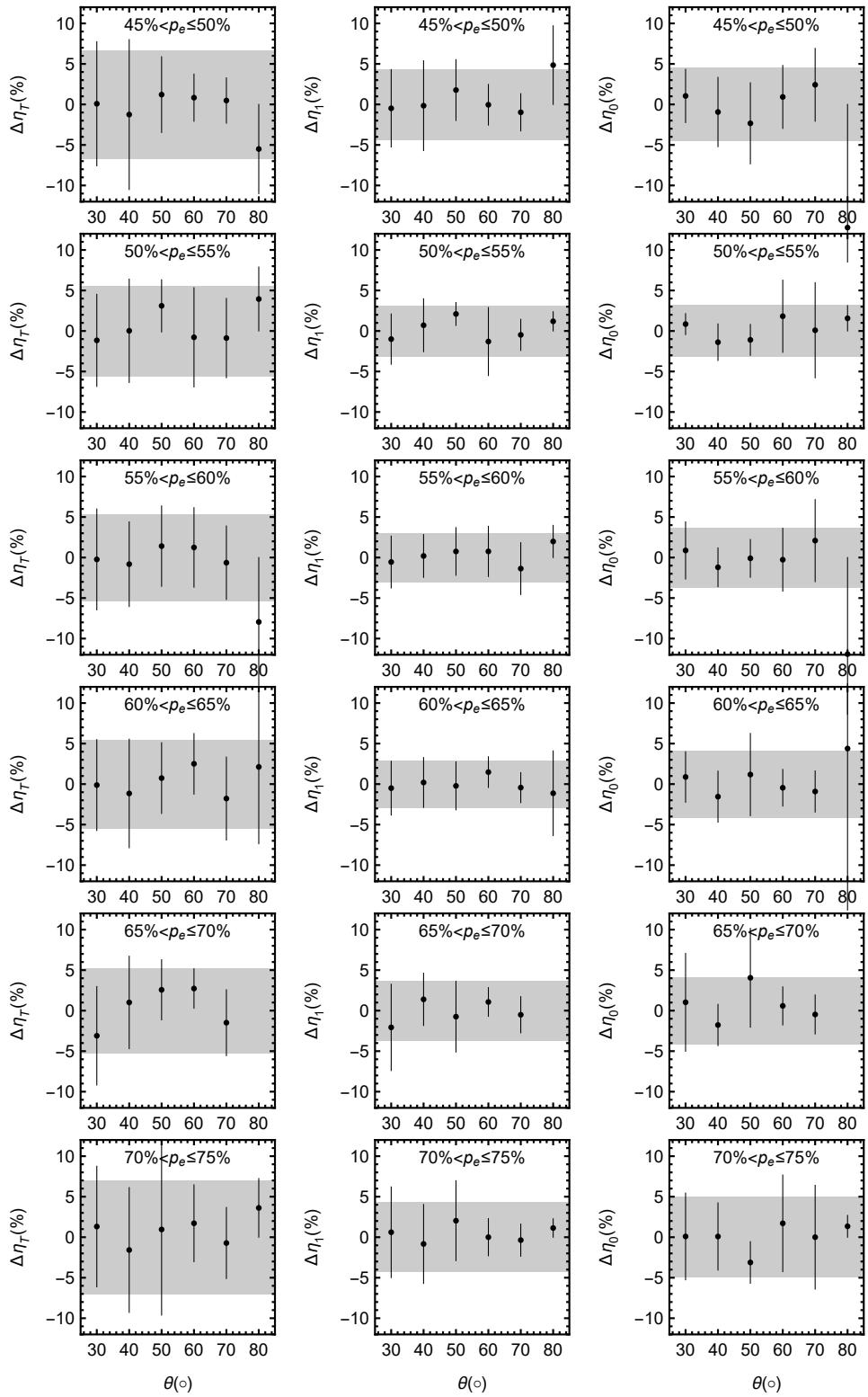


Fig. S3. Fit residuals as a function of grating diffraction angle (i.e. $\theta = \arcsin(\lambda/d)$).

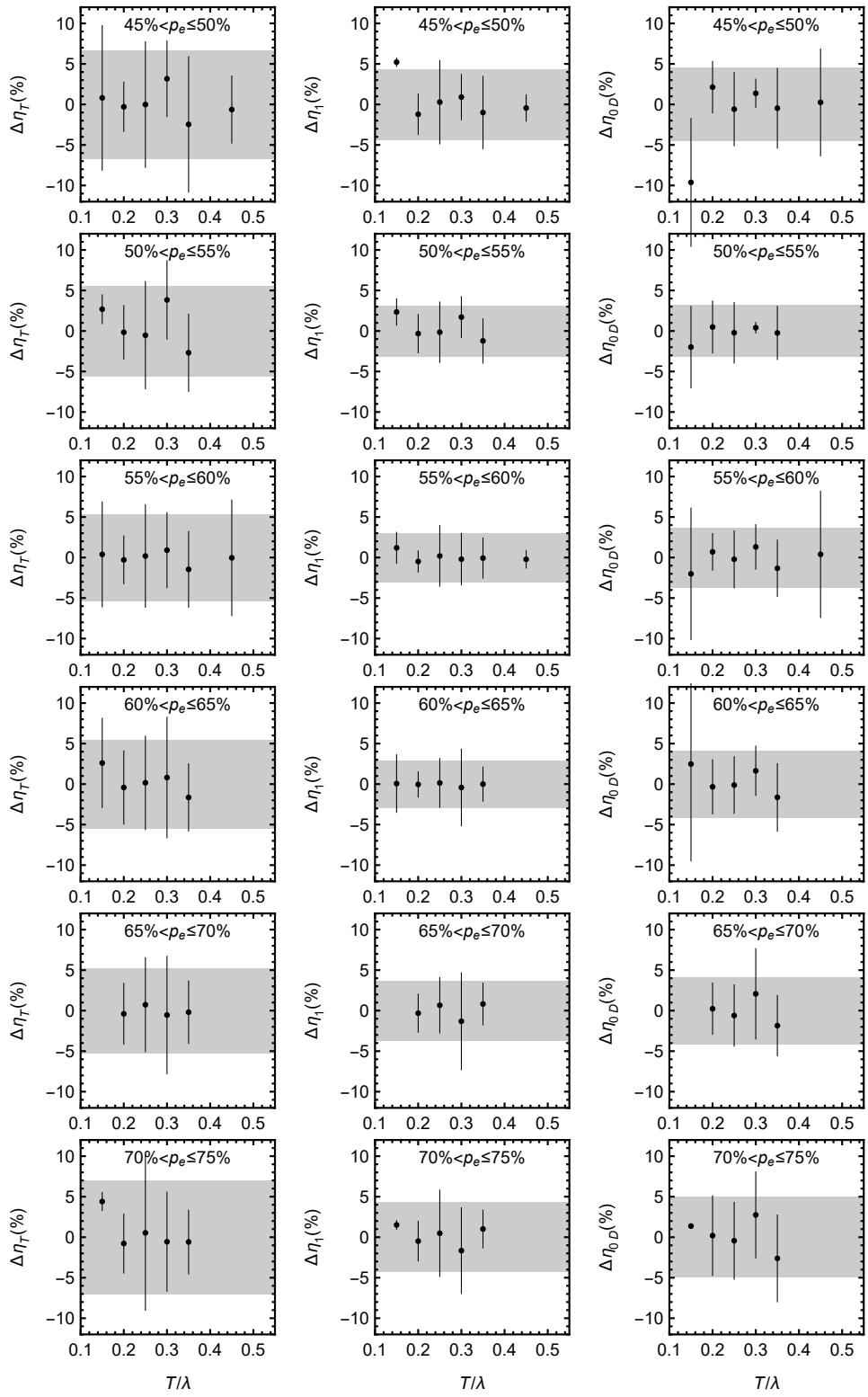


Fig. S4. Fit residuals as a function of dimensionless grating etch depth T/λ .